

What is claimed is:

1. An optical recording medium which comprises at least a recording layer comprising an organic dye, a reflecting layer composed of a metal, and a protective layer laminated in this order on a light-transmittable substrate, wherein the reflecting layer is a thin film comprising silver as a major component and satisfying a relationship of $I(200)/I(111) > 0.40$ when an X-ray diffraction intensity by a (111) plane is designated as $I(111)$ and an X-ray diffraction intensity by a (200) plane is designated as $I(200)$ in an X-ray diffraction spectrum measured by a θ - 2θ method while an angle of incidence with reference to a surface of the light-transmittable substrate is set at θ .

2. The optical recording medium according to claim 1, wherein a depth of a groove formed on the light-transmittable substrate is from 150 to 200 nm, and a width of the groove is from 0.2 to 0.4 μm .

3. The optical recording medium according to claim 1, wherein a groove pitch is from 0.5 to 1.5 μm .

4. The optical recording medium according to any one of claims 1 to 3, wherein the organic dye in the recording layer is an azo type dye and/or a cyanine type dye.

5. A method for producing an optical recording medium which comprises at least a recording layer comprising an organic dye, a reflecting layer composed of a metal by a sputtering method, and a protective layer laminated in this order on a light-

transmittable substrate, said method comprising the step of forming a thin film comprising silver as a major component and satisfying a relationship of $I(200)/I(111) > 0.40$ when an X-ray diffraction intensity by a (111) plane is designated as $I(111)$ and an X-ray diffraction intensity by a (200) plane is designated as $I(200)$ in an X-ray diffraction spectrum measured by a θ - 2θ method while an angle of incidence with reference to a surface of the light-transmittable substrate is set at θ , by controlling a sputtering gas pressure in a sputtering chamber in forming the reflecting layer by the sputtering method.

6. The method for producing an optical recording medium according to claim 5, wherein the sputtering gas pressure in the sputtering chamber is set within a range from 0.23 to 1.00 Pa.